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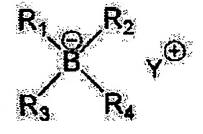
**DEMACHI YASUYUKI** 

## (54) VISIBLE LIGHT POLYMERIZABLE COMPOSITION

## (57)Abstract:

PROBLEM TO BE SOLVED: To obtain the subject composition having a high photosensitivity and a high photosensitive rate in a long wavelength region and approaching a colorless and transparent state after photosetting by including a compound having a radically polymerizable ethylenically unsaturated bond, a specific onium salt, a coloring matter and boronic acid ammonium salt.

SOLUTION: This composition is obtained by including (A) a compound having a radically polymerizable ethylenically unsaturated bond (e.g. itaconic acid), (B) an aromatic onium salt capable of generating a Broensted acid or a Lewis acid for activating a radical species and a cationic polymerization when exposed to actinic radiations (e.g. diphenyl iodonium), (C) a coloring matter having a molecular structure conjugated with a dialkylamino group and capable of spectrally sensitizing the component B (e.g. 7-diethylamino-3-benzoylcoumarin) and (D) a boronic acid ammonium salt represented by the formula [R1, R8, R3 and R4 are each a (substituted)alkyl, a (substituted)allyl, silyl, a heterocyclic ring



(substituted)alkyl, a (substituted)allyl, silyl, a heterocyclic ring or the like; Y+ is a metal cation or the like].

## **LEGAL STATUS**

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